

### **CERN Workshop upgrade status**

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WG6

- Equipment upgrade
- New building

### WG6: TE/MPE/EM Workshop upgrade

Last year, agreement was reached with CERN management to purchase the subset of machines necessary to carry out R&D on large size GEM (2m x 0.5 m) & Micromegas (2m x 1m) and the associated large size read-out boards in the current CERN TE/MPE/ME facility.

•	GEM	market survey	call for tender	order	received	ready
	<ul> <li>1 continuous polyimide etcher</li> </ul>	X	X	X	X	01/2012
	<ul> <li>1 Cu electro-etch line</li> </ul>	x	x	x	X	X
	<ul> <li>1 stripping line</li> </ul>	x	x	x	X	X
•	Micromegas					
	<ul> <li>1 large laminator</li> </ul>	X	X	x	X	X
	- 1 large Cu etcher	X	X	X		01/2012
	<ul> <li>1 large UV exposure unit</li> </ul>	X	X	X	X	12/2011
	<ul> <li>1 large resist developer</li> </ul>	X	X	X		01/2012
	<ul> <li>1 large resist stripper</li> </ul>	X	X	X		01/2012
	<ul> <li>1 large oven</li> </ul>	x	x	x	X	X
	<ul> <li>1 large dryer</li> </ul>	x	x	x	X	X

- •On top of introducing new machines we have to:
  - -redefine all the process parameter related to the new equipments
  - -Build some prototypes of the # detectors
  - -A fellow is already selected and will start running machines beginning of 2012

#### **Machine investment for GEM production**



 •UV exposure unit moving from 2m x 0.6m → 2.2m x 1.4m
 30 years old equipment replacement TECHNIGRAPH (DE)

Not yet Installed Already delivered



•GEM alcohol resist stripping 1m x 0.6m → 2.2m x 0.6m

•GEM electro etch

1m x 0.6m → 2.2m x 0.6m

10 baths compacted

LECOULTRE (CH)







•GEM polyimide etch moving from 1m x 0.6m → ? 10→ 30 GEM/day roll to roll compatible no tooling needed WISE (IT)





#### **Machine investment for Micromegas production**



•Laminator (resist and coverlay)
0.6m width → 1.4m
WESTERN MAGNUM (US)





•Ovens (cure the coverlay)
1.5m x 0.6m → 2.2m x 1.4m
JLS (UK)





- Resist developer
- Resist stripper
- Copper etcher

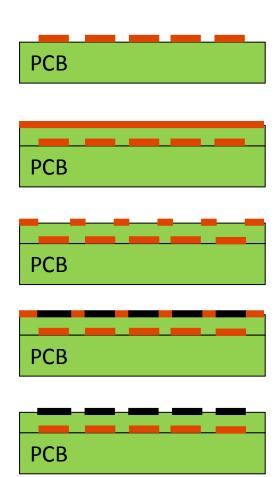
0.6m width  $\rightarrow$  1.2m

WISE (IT)

Not yet delivered ordered

### **Resistive deposition equipment**

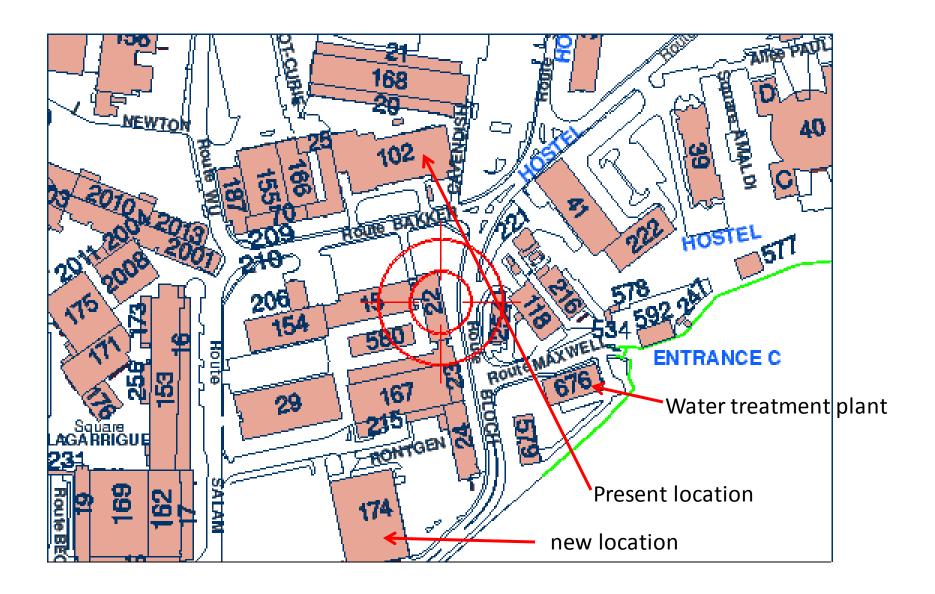
- •This process was not existing when we ask for the subset of machines
- Different techniques are envisaged:
  - Paste filling + polishing (no size limitation)
  - Screen printing (80cm x80cm)
  - Spray deposition (no equipment at CERN)
- •In the coming month we are going to study the best solution for mass production.



- Equipment upgrade
- New building

### New Building 107





# New Building 107



### New Building 107



CERN Building 107
Basis of Design

#### **New building 107**

- The construction should start beginning of 2012
- •The construction should end November 2013
- •40 square meter room reserved for MPGD assembly
- •All the machines for large size detectors production are in the layout
- •Area 900 m2 → 1400m2 with optimized layout
- Most of the baths will be replaced by compact machines
- Rooms are reserved for new processes (laser and plasma)

## Thank you